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ABSTRACT OF THE DISCLOSURE (FIG. 4)

"PHOTORESIST COATING METHOD AND APPARATUS"

A resist coating method for forming a resist film
on a substrate by supplying a resist solution to
5 substantially a center of a substrate surface while the
substrate is rotated, rotating the substrate at a low
speed by decelerating the rotation of the substrate
after the supply of the resist solution is terminated,
rotating the substrate at a high speed by accelerating
10 the rotation of the substrate after the substrate is
rotated at the low speed for a predetermined time-
period.

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